

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant:	Hyun-Woo Kim et al.	Examiner: Amanda C. Walke
Serial No:	10/787,368	Group Art Unit: 1752
Filed:	February 26, 2004	Docket: 8028-42 (SPX200304-0017US)
For:	<b>METHOD OF FORMING AN UNDERLAYER OF A BI-LAYER RESIST FILM AND METHOD OF FABRICATING A SEMICONDUCTOR DEVICE USING THE SAME</b>	

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE**

Sir:

This paper is being filed in response to the Office Action mailed on November 14, 2006.

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